Surface-enhanced optical third-harm onic generation in Ag island Im s

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(Dated: April 14, 2024)

Surface-enhanced optical third-harm onic generation (THG) is observed in silver island lm s. The THG intensity from Ag nanoparticles is enhanced by more than two orders of magnitude with respect to the THG intensity from a smooth and hom ogeneous silver surface. This enhancement is attributed to local plasm on excitation and resonance of the local eld at the third-harm onic wavelength. The di use and depolarized component of the enhanced THG is associated with the third-order hyper-Rayleigh scattering in a 2-D random array of silver nanoparticles.

PACS num bers:

Observation of surface-enhanced nonlinear optical effects in silver island Im s dates back to two 1981 papers by W okaun, et al., [1,2], where surface-enhanced optical second-harm onic generation (SHG) and surfaceenhanced Ram an scattering (SERS) were observed in silver island Im s. The enhancement of the SHG intensity by up to three orders of magnitude was attributed in [1] to the resonant enhancem ent of the local eld at the second-harm onic (SH) wavelength, mediated by the excitation of the local surface plasm ons in silver nanoparticles. This plasm on mechanism of the local eld enhancem ent, introduced by Berrem an [3] and M oskovits [4], was intensively discussed in the context of SERS active structures and surface-enhanced SHG from electrochem ically roughened silver surfaces [5] and rough surfaces of other m etals [6]. A coording to this approach, nonlinear polarization of a rough m etal surface or an array of sm allm etal particles is given by: $P_{2!} = L_{2!}$ (2) (2!) $L_1^2 E_1^2$ at the SH wavelength and $P_{3!} = L_{3!}$ ⁽³⁾ (3!) $L_{!}^{3} E_{!}^{3}$ at the thirdharm onic (TH) wavelength, where (2) (2!) and (3) (3!) are the second-and third-order susceptibilities of m etal, respectively; E is the optical eld at fundam entalw avelength; and L_1 , L_2 and L_3 are the local eld factors at the corresponding wavelengths.

The spectral dependence of the local eld factor of an array of sm all m et al spheroids embedded in a dielectric m atrix within the simple approach in dipole and e ective m edia approximations, is given by [7]:

$$L() = \frac{"_{d}()}{"_{d}() + ["_{m}()] + ["_{d}()]}$$
(1)

where $"_d()$ and $"_m()$ are the dielectric constants of the dielectric matrix and of the metal, respectively; N is the shape-dependent depolarization factor of the spheroids; and q is the lling factor, i.e., the relative fraction of the metal in a composite material. The resonant wavelength of the local eld factor, res, corresponds to set-

ting the real part of the denom inator in Eq. 1 to zero: $Re["_d(_{res}) + ["_m(_{res}) "_d(_{res})]N q=3)]= 0$. For an isolated small Ag sphere in vacuum $_{res}$ 200nm. Three factors result in the red-shift of $_{res}$ up to the visible range for an array of particles: (1) the distortion of the particle shape, (2) the dipole-dipole interaction between particles and, (3) an increase in the dielectric constant of them atrix m aterial. The resonant increase of the local eld factor at $_{res}$ results in a many-fold increase of the nonlinear-optical response from a nanoparticle array.

Up to the present time, the experimental studies of local plasm on enhancement in island Im swere restricted to SERS and SHG.Fig. 1d, taken from [1], shows the dependencies of the local eld factor in Ag island Im som mass thickness, $d_m = m = ,$ where m is the mass of metal deposited per unit area and is the bulk density of Ag. These dependencies show the maximum at $d_m = 2.0$ nm and $d_m = 6.0$ nm for wavelengths of 532 nm and 1064 nm, respectively. The decrease of d_m results in the blue-shift of res due to a decrease of interparticle interaction. One m ight anticipate that the resonance at THG wavelength res = 355 nm for the 1064 nm fundamental wavelength can be attained for d_m Inm.

A nother peculiarity of the surface-enhanced SHG from m etal island lms is the di useness of the SH radiation [5,6]. This is a manifestation of the second-order hyper-Rayleigh scattering. Silver island lms are random arrays of nanoparticles which possess random spatial inhom ogeneity of nonlinear susceptibilities [8] and local eld factors [9]. This inhom ogeneity is the source of the di use SHG radiation in hyper-Rayleigh scattering.

The enhancement and di useness observed, up to now, for SHG are general features of the nonlinear optical effects in island lm s and are supposed to be observed in THG. Meanwhile, in spite of this analogy, there is a principle di erence between SHG and THG in metal nanoparticles: ⁽²⁾ is localized at the surface of nanoparticles and vanishes in the bulk of a centrosymmetric metal, whereas ⁽³⁾ is a bulk localized nonlinearity [10], as shown schematically in the inset in Fig. 1a.

In this paper, surface-enhanced THG and third-order

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hyper-Rayleigh scattering is observed in Ag island Ims. The resonant plasm on mechanism of the THG enhancement is proved.

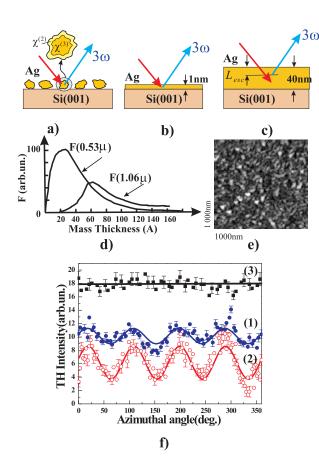


FIG.1: Schem atics of a) silver island Im (inset in (a) shows the localization of $^{(2)}$ and $^{(3)}$ in nanoparticles); b) model of hom ogeneous Im of the equivalent thickness of 1 nm; c) hom ogeneous reference Ag Im with a thickness of 40 nm and an escape depth of $L_{esc} = 7nm$ for the TH wave at the fundam ental wavelength ! = 1064nm; d) dependencies of the local eld factors at wavelengths of 1.064 m and 0.532 m on the mass thickness (from [1]); e) the AFM image of silver island Im; f) the THG intensity as a function of the azim uthal angle from: (1) silver island Im on Si(001) substrate, (2) silver-free Si(001) substrate, (3) hom ogeneous reference Ag Im with a thickness of 40 nm; the solid lines are results of approxim ations.

The Im s were prepared by them alevaporation of silver onto the substrates of silicon Si(001) wafers at a rate of 3-4 A =s and residual pressure of 10⁵ Torr. The silicon wafers were chosen as substrates because of, rst, the atness and hom ogeneity of the surface, and, second, the sim plicity of the chem ical etching procedure that is used for the preparation of a step-like SiO₂ wedge (see the scheme in Fig. 2b). Three types of Ag Im s are studied:

Ag island $\,$ Im with a mass thickness of $q_{\rm m}$ $\,$ 1 nm and expected plasm on resonance at $_{\rm res}$ $\,$ 355 nm , Ag island

In with plasm on resonance in the vicinity of $_{res}$ 270 nm on the silicon oxide step-like wedge, and a thick homogeneous Ag reference In with a thickness of 40 nm. The thick homogeneous Ag Im is used as a reference source of non-enhanced bulk THG for the measurement of the THG enhancement from island Ims. An atom ic forcem icroscopy (AFM), in the constant forcem ode, and with a height resolution of 1 nm and lateral resolution of approximately 10 nm, is used to characterize the morphology of the samples. Fig. 1e shows the AFM image of Ag island Im. A cross-section of the pro le show sthat the average lateral size and height of silver nanoparticles is about 40 nm and 3 nm, respectively.

The outputs of two laser systems are used as the fundam ental radiation in the THG and SHG experiments: (1) an OPO laser system, "Spectra-Physics 710," with a wavelength which is tunable in the spectral range from 490 nm to 680 nm, a pulse duration of 4 ns, and a pulse intensity of 2 M W /cm²; and (2) a Q -sw itched YAG \mathbb{N} d³⁺ laser tuned to a 1064 nm wavelength, a pulse duration of 15 ns, and a pulse intensity of about $1 \text{ MW} / \text{cm}^2$. The TH (SH) radiation is ltered out by appropriate UV and BG color and bandpass lters and detected by a PMT and gated electronics. To norm alize the THG (SHG) intensity over the OPO and YAG $\mathbb{N} d^{3+}$ laser uency, and the spectral sensitivity of the optical detection system, a reference channel is used with a Z-cut quartz plate as a nonlinear optical reference and with a detection system identical to that of the "sam ple" channel. Polar rotation of the detector system enables us to measure the linear Rayleigh scattering pattern and the THG and SHG scattering patterns (see Fig. 2a).

In order to observe and measure an enhancement in THG, two experimental points have to be taken into account: (1) the THG signal from Ag island in should be distinguished from the Si(001) substrate contribution and (2) the THG intensity should be integrated over the diffuse THG scattering pattern. The following paragraphs focus on these points.

The curve (1) in Fig. 1f shows the azim uthal dependence of the THG intensity from the sample of Ag island

In in the specular direction for the s-in, s-out combination of polarizations of the fundam ental and TH waves. The anisotropic component of the THG signal is related to the nonlinear response of Si(001) substrate, whereas the isotropic THG is attributed to both Ag nanoparticles and Sisubstrate. To distinguish the THG contribution of Ag island Im from that of the substrate, the azim uthal dependence of the THG intensity from Si(001) is measured in the same s-in, s-out geom etry (curve (2) in Fig. 1f). The ratio of the anisotropic components of THG from silver island Im on Si(001), $I_{\rm IF+Si}^{\rm anis}$ (3!), and silverfree Si(001) substrate, $I_{\rm Si}^{\rm anis}$ (3!), gives an attenuation co-e cient of the THG response from substrate due to the absorption and scattering in the silver coverage: 3! = $I_{\rm IF+Si}^{\rm anis}$ (3!)= $I_{\rm Si}^{\rm anis}$ (3!) = 0:46. The estimation of the 3!

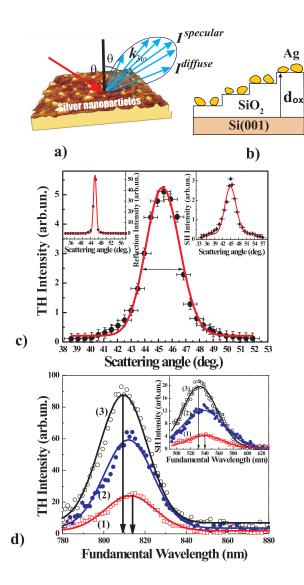


FIG .2: a) The scheme of the hyper-Rayleigh scattering experim ent; b) schem e of silicon oxide step-like wedge as a variable spacer between the island Im and the high-dielectric constant m aterial (silicon); dox is the thickness of the silicon oxide steps; c) THG scattering pattern: the THG intensity from the island Im as a function of polar scattering angle (angular 0:5); left inset is the linear Rayleigh scatterwidth is 3 ing pattern, with angular width of 1 0:5; right inset is the SHG scattering pattern, with angular width of 5 0:5 ; solid lines are approximations with Eq. 3; d) main panel: dependencies of the THG intensity on the fundam ental wavelength for A g island Im s deposited on the SiO 2 step-like wedge for $d_{ox} = 2 \text{ nm}$ (1), 70 nm (2) and 100 nm (3); inset: the same for the SHG intensity spectra; solid lines are approximations by Gaussian function.

coe cient is the state in the determination of the THG enhancement for Ag island Im s. The relative value of the THG intensity from Ag nanoparticles in the specular direction is $I_{IF}^{spec}(3!) = I_{IF+Si}^{is}(3!) = J_{Si}^{is}(3!)$ where $I_{IF+S_{i}}^{is}(3!)$ and $I_{S_{i}}^{is}(3!)$ are the isotropic components of THG from the island Im on Si(001) and from silver-free substrate, respectively. O btaining the total intensity of the di use THG from Ag nanoparticles is the second step in the determ ination of the THG enhancement. This dem ands the measurement of the THG scattering pattern which is dependent on the di use THG intensity, which in turn depends on the polar scattering angle: I_{IF} (3!;) = I_{IF}^{spec} (3!)S_{3!} (), where and $S_{3!}$ () are the polar scattering angle and the norm alized form -factor of the third-order hyper-Rayleigh scattering, respectively. The main panel in Fig. 2c shows the experim ental scattering pattern of di use THG from silver island Im s where the angular width of the norm alized form -factor is approxim ately 3 0:5. This su ciently exceeds the angular width of 1 0:5 of the scattering pattern of linear Rayleigh scattering from the same silver island Im presented in the left inset in Fig. 2c, whereas the angular width of the SHG scattering pattern is approximately 5 0:5. The total intensity of the di use THG can be obtained by angular integration of the THG scattering pattern and in the case of the sm all angular width of $S_{3!}$ (), is given by: $I_{\rm F}$ (3!) = I_{IF}^{spec} (3!) [- $S_{3!}$ () d² 0:6 1 $\theta I_{TE}^{\text{spec}}$ (3!), where

is an angular aperture of the THG detection system and

is the angular interval of integration. To estim ate quantitatively the THG enhancement, we consider the total THG intensity of the specular THG from a model hom ogeneous lm with an equivalent thickness of $d_m = 1$ nm and compare this with the THG intensity from a reference lm with a thickness of 40 nm (see Fig. 1b and c). The THG intensity detected from the reference

In comes from the Ag layer corresponding to the escape depth L_{esc} of the TH wave (curve (3) in Fig. 1f). In our experimental conditions, $L_{esc} = 7 \text{ nm}$ for $_{3!} = 355 \text{ nm}$. Thus, the enhancement of the THG intensity from Ag island Im with respect to a thick hom ogeneous Ag Im is given by:

$$G = \frac{I_{IF}(3!)}{I_{ref}(3!)} \frac{{}^{"}R_{40} \exp (3! + 3!)r]dr}{{}^{"}R_{1} \exp (3! + 3!)r]dr}$$
 1.2 10;
(2)

where I_{ref} (3!) is the THG intensity from reference Ag Im, 1 and 31 are adsorption coe cients at the fundam ental and TH wavelengths, respectively, and r is co-ordinate norm alto the Im surface.

To prove the plasm on assistance in the THG enhancement, the dependencies of the THG intensity on the fundam ental wavelength are studied for Ag island Im s deposited onto a step-like SiO₂ wedge on silicon wafer. Silicon oxide steps serve as variable spacers between the silver nanoparticles and silicon substrate, which is a high-

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dielectric constant material. Variations of SiO₂ thickness, d_{ox} , result in the variations of the e ective dielectric constant $"_{d1}(d_{ox}) = "^0_{d1}(d_{ox}) + i "^0_{d1}(d_{ox})$ in Eq. 1: the increase of d_{ox} corresponds to the decrease of the e ective $"_{d1}(d_{ox})$. Theoretical modeling [11] shows that the decrease of the real part, $"^0_{d1}(d_{ox})$, results in the blueshift of the resonant plasm on wavelength, whereas the decrease of the imaginary part, $"^0_{d1}(d_{ox})$, leads to the enhancement of the local eld amplitude.

The main panel in Fig. 2d shows a set of THG spectra for dox increasing in the range from 2 nm to 100 nm. The observed e ects of d_{0x} on the THG spectra as SiO₂ thickness increases from 2 nm to 100 nm is two-fold: (1) an apparent blue-shift of approxim ately 6 nm of the THG resonance and, (2) a m ore than four-fold increase of the THG resonant intensity. These changes correspond to the decrease of the e ective dielectric constant of A g islands situated at di erent steps of the SiO_2 wedge. An analogous blue-shift of about 10 nm and manyfold increase of the resonant SHG intensity are observed in the sam e conditions (refer to the inset in Fig. 2d). The im pact of the dielectric constant of the substrate on the resonant properties of surface-enhanced THG and SHG proves the plasm on-assisted mechanism of the enhancement. A slight di erence in the spectral shift for THG and SHG can be associated with the di erent localizations of ⁽³⁾ and ⁽²⁾ in m etal nanoparticles. M oreover, di erent spatial localizations of nonlinear susceptibilities in metal particles can result in di erent parameters of scattering patterns at the TH and SH wavelengths from a random array of Aq nanoparticles. Norm alized form factors at the TH and SH wavelengths are given by:

 $S_{3!;2!} () = \exp[M_{3!;2!} k_{3!;2!}^2 l_{cor}^2 (3!;2!)]; \quad (3)$

where l_{cor} (3!;2!) is the correlation length at the TH and SH wavelengths, respectively, $k_{3!,2!} = 2$ (sin \sin_0) = 31;21 and M 31;21 is an adjustable parameter at the TH and SH wavelengths, respectively; and $_0$ is the angle of incidence. The approximation of the diffuse THG and SHG scattering patterns (Fig. 2c, solid lines) by Eq. 3 corresponds to the correlation lengths of $l_{cor}(3!)$ 42 nm and l_{cor} (2!) 20 nm. The former probably corresponds to the average Ag particle size of 40 nm obtained from the AFM m easurem ents because of the bulk localization of ⁽³⁾. Meanwhile, the latter being twice as sm all as l_{cor} (3!), corresponds to the sm aller scale of the ⁽²⁾ inhom ogeneity due to its surface localization within the individual particles.

In conclusion, surface-enhanced THG is observed in Ag island Im s with an enhancement of 1.2 1²Q which is attributed to the local surface plasm on excitation in Ag nanoparticles at the TH wavelength. Di useness of surface-enhanced THG allows us to associate this e ect with the third-order hyper-R ayleigh scattering in a random array of nanoparticles. The di erence in scattering patterns and spectroscopic resonances between surface-enhanced THG and SHG can be attributed to the di erent localizations of $^{(3)}$ and $^{(2)}$ in nanoparticles. A cknow ledgm ents

This work is supported in part by the Russian Foundation for Basic Research (Grants No. 04-02-16847, 04-02-17059, 03-02-39010), the Presidential Grants for Leading Russian Science Schools (No. 1604 2003 2 and 1909 2003 2), the DFG Grant No. 436 RUS 113/640/0-1, the NATO Grant PST CLG 979406 and the INTAS Grant No. 03-51-3784.

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